

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	18	("6328634") or ("6443812") or ("6503418") or ("6530824") or ("20010024933") or ("20020019202") or ("20020132563") or ("20040171265") or ("0114496")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/08/09 13:40
S2	0	(@ad<="20041217") and S1 and ((polyvinylalcohol or "polyvinyl alcohol") same copolymer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/05/17 17:33
S3	1	(@ad<="20041217") and S1 and ((polyvinylalcohol or "polyvinyl alcohol"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/09 13:53
S4	1	(@ad<="20041217") and S1 and ((polyvinylalcohol or "polyvinyl alcohol")) and "vinyl alcohol" and silica	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/09 14:00
S5	4	(@ad<="20041217") and S1 and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol")) and "vinyl alcohol" and silica	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/08 10:35
S6	99	(@ad<="20041217") and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol" or PVA)) and "vinyl alcohol" and silica and CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/05/17 12:42
S7	6	(@ad<="20041217") and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol" or PVA) near copolymer) and "vinyl alcohol" and silica and CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/09 15:52
S8	11	(@ad<="20041217") and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol" or PVA) near2 copolymer) and "vinyl alcohol" and silica and CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/09 15:59
S9	9	(@ad<="20041217") and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol" or PVA) near2 copolymer) and "vinyl alcohol" and silica and CMP and hydroph\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/09 16:00

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S10	20	(US-20060135045-\$ or US-20050076581-\$ or US-20040203324-\$ or US-20040065022-\$ or US-20040014319-\$ or US-20030181046-\$ or US-20030124959-\$ or US-20020173243-\$ or US-20020173241-\$ or US-20020005504-\$ or US-20010024933-\$).did. or (US-6443812-\$ or US-6918820-\$ or US-6821897-\$ or US-6786945-\$ or US-6720264-\$ or US-6568997-\$ or US-6503418-\$ or US-6328634-\$).did. or (US-20060135045-\$).did.	US-PGPUB; USPAT; DERWENT	OR	ON	2006/08/10 10:36
S11	12	S10 and (polyacetals polyacrylics polycarbonates polystyrenes polyesters polyamides, polyamideimides polyarylates polyarylsulfones polyethersulfones polyphenylene\$1sultides polysulfones polyimides polyetherimides polytetrafluoroethylenes polyetherketones polyether\$1etherketones polyether\$1ketone ketones polybenzoxazoles polyoxadiazoles polyberothiazinophenothirines polybenzothiazoles polypyrazinoquinoxalines polypyromellitimides polyquinoxalines polybenzimidazoles polyoxindoles polyoxoisindolines polydioxoisindolines polytriazines polypyridazines polypiperazines polypyridines polypiperidines polytriazoles polypyrazoles polycarbonates polyoxabicyclononanes polydibenzofurans polyphthalides polyacetals polyanhydrides polyvinyl\$1ethers polyvinyl\$1thioethers polyvinyl\$1ketones polyvinyl\$1halides polyvinyl\$1esters polysulfonates thermoplastic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:23
S12	5	S10 and hydrolysis	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:24
S13	1	S10 and hydrolysis and polyvinylalcohol	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:25
S14	5	S10 and hydrolysis and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol"))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:26
S15	1	S10 and (hydrolysis same ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol")))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:26
S16	1	S10 and (hydrolysis with ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol")))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:26
S17	3893	((@ad<="20041217") and (hydrolysis same ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol")))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:29

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S18	19	(@ad<="20041217") and (hydrolysis same ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol")))) and CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/08/10 12:29
S19	2	("20060135045").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/12/08 07:25
S20	47	(@ad<="20041217") and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol" or PVA)) and "vinyl alcohol" and silica and CMP and copper	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/08 08:12
S21	2	("6786945").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/12/08 10:33
S22	7	(@ad<="20041217") and (corrosion with vinylimidazole)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/12/08 10:37
S23	2	("20060135045").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/05/17 11:32
S24	38	(@ad<="20041217") and (\$5idazole with copper) and CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/05/17 12:43
S25	12	(@ad<="20041217") and (\$5idazole with copper with corrosion) and CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/05/17 12:44
S26	2517	(@ad<="20041217") and (438/692.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/05/17 17:35
S27	9	(@ad<="20041217") and (438/692.ccls.) and ((polyvinylalcohol or "polyvinyl alcohol" or "poly\$1vinyl\$1alcohol" or PVA)) and "vinyl alcohol" and silica and CMP	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/05/17 17:35

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S28	2	("6077787").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR.	OFF	2007/08/14 13:08
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EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2059	nanowires	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 06:55
S2	1272	nanowires and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 13:00
S3	245	nanowires and semiconductor and dispersion	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 13:00
S4	87	(@ad<="20021118") and nanowires and semiconductor and dispersion	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 13:36
S5	53	(@ad<="20021118") and nanowires and semiconductor and dispersion and etch\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 13:02
S6	28	(@ad<="20021118") and nanowires and semiconductor and dispersion and etch\$4 and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 10:13
S7	28	(@ad<="20021118") and nanowires and semiconductor and dispersion and etch\$4 and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/05 17:01
S8	0	(@ad<="20021118") and (manufacturing adj nanowires) and semiconductor and dispersion and etch\$4 and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 13:16
S9	0	(@ad<="20021118") and (manufactur\$4 with nanowires) and semiconductor and dispersion and etch\$4 and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 13:16
S10	145	(@ad<="20021118") and nanowires and semiconductor and etch\$4 and mask	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 15:13

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S11	75	(@ad<="20021118") and nanowires and semiconductor and etch\$4 and mask and anod\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 17:42
S12	16	(@ad<="20021118") and nanowires and semiconductor and etch\$4 and mask and anodically	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 17:42
S13	3	(@ad<="20021118") and nanowires and semiconductor and etch\$4 and mask and (anodically with etch\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/06 12:48
S14	35	(@ad<="20021118") and nanowires and semiconductor and etch\$4 and mask and ((anodically or electrochemical\$4) with etch\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 18:20
S15	117	(@ad<="20021118") and (nanowire or nanotube or nanostructure) and semiconductor and etch\$4 and mask and ((anodically or electrochemical\$4) with etch\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/28 18:21
S16	14	("2001/0054709").URPN.	USPAT	OR	ON	2006/03/28 18:31
S17	14	("2001/0054709").URPN.	USPAT	OR	ON	2006/03/28 18:33
S18	14	("2001/0054709").URPN.	USPAT	OR	ON	2006/03/28 18:34
S19	257	nanowires and oxidation and etch	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 06:55
S20	25	"5607876"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 09:31
S21	14	(@ad<="20021118") and nanowires and semiconductor and dispersion and vibration	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 10:58
S22	65	(@ad<="20021118") and nanowires and semiconductor and dispersion and (vibrat\$4 or ultrasonic or ulta or remov\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 11:03

EAST Search History

S23	24	(@ad<="20021118") and nanowires and semiconductor and dispersion and (vibrat\$4 or ultrasonic or ulta)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 12:11
S24	27	(@ad<="20021118") and nanowires and sol-gel	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 14:39
S25	0	Van-den-meerakker.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 14:40
S26	0	(Van-den-meerakker.in.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 14:41
S27	0	(blaaderen-alfons.in.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 14:41
S28	0	(carlos-maria-van-kats.in.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 14:41
S29	474739	(Van den meerakker.in.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 14:42
S30	31	(meerakker.in.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/03/29 14:42
S31	4	((("5987208") or ("5607876")).PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/09/13 18:13
S32	2	("5607876").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/03/05 16:51

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S33	234	(@ad<="20021118") and nanowires and etch\$4 and (holes or pores)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/05 17:02
S34	1	(@ad<="20021118") and nanowires and substrate and dispersion and coloring	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/03/06 12:49
S35	95	(@ad<="20021118") and (nanowires with etch\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 09:48
S36	665	(@ad<="20021118") and (438/691.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:40
S37	10	(@ad<="20021118") and (438/691.ccls.) and nano	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 10:14
S38	1	(@ad<="20021118") and (438/691.ccls.) and nanowire	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 10:15
S39	137	(@ad<="20021118") and ("438"/\$.ccls.) and nanowire	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 10:17
S40	23	(@ad<="20021118") and ("438"/\$.ccls.) and (nanowire same etch\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 10:24
S41	2	("6359288").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/08/13 13:12
S42	131	(@ad<="20021118") and (nanowire same etch\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 10:24

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S43	2	("20030098640").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/08/13 12:09
S44	2	("6221777").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/08/13 13:12
S45	75	(@ad<="20021118") and nanowires and semiconductor and dispersion and (um or micron or micrometer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/13 15:39
S46	23	(@ad<="20021118") and nanowires and semiconductor and dispersion and ((um or micron or micrometer) with length with nanowire)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/14 11:52
S47	2	("20040065022").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/08/14 11:52
S48	2	("20020176276").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/08/14 17:04
S49	270	(@ad<="20021118") and (216/56.ccls.)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:40
S50	29	(@ad<="20021118") and (216/56.ccls.) and nano\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:45
S51	12	(@ad<="20021118") and ("216"/\$3.ccls.) and nanowires	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:51
S52	28	(@ad<="20021118") and ("205"/\$3.ccls.) and nanowires	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:51